

INFORMATION DISCLOSURE CITATION IN AN *NOIPE* APPLICATION

(PTO-1449)

DEC 10 2003



ATTY. DOCKET NO.
63979-028

SERIAL NO.
10/616,917

APPLICANT
Takashi NISHIKAWA, et al.

FILING DATE
July 11, 2003

GROUP
2811

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		US 2001/0028582 A1	10/11/2001	Tanai et al.	
		US 6,407,435 B1	06/18/2002	Ma et al.	
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			

duplicate

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date M of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	T14ranslation	Yes	No
<i>duplicate</i>	A	JP 06-204484	07/22/1994	HITACHI LTD	Japanese (w/ English Abstract)		
<i>KR</i>		JP 11-168089	06/22/1999	SONY CORP	Japanese (w/Partial English Translation & Abstract)		
<i>duplicate</i>	A	JP-P2002-313966	10/25/2002	NIPPON PRECISION CIRCUITS INC	Japanese (w/ English Abstract)		
<i>duplicate</i>		EP 1124262	08/16/2001	SHARP KABUSHIKI KAISHA			

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		Mitsue Takahashi et al., "ANALYSIS AND IMPROVEMENT OF RETENTION TIME OF MEMORIZED STATE OF METAL-FERROELECTRIC-INSULATOR-SEMICONDUCTOR STRUCTURE FOR FERROELECTRIC GATE FET MEMORY", The Japan Society of Applied Physics, January 5, 2001, pp. 2923-2927

duplicate

EXAMINER

DATE CONSIDERED

K. Rose

Sept. 22, 2002

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

